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Sheet <u>1</u> of <u>1</u>			Application Number	
			Filing Date	09/27/2001
			First Named Inventor	Albert Edward Moore, Jr.
			Group Art Unit	IPEA
			Examiner Name	Not Assigned
			Attorney Docket Number	Moore.A-02

C985 U.S. PTD  
 09/26/56  
 09/27/01

[illegible][illegible]

Examiner Signature	<i>Sin J. Lee</i>	Date Considered	7-23-'03
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup> Unique citation designation number. <sup>2</sup> See attached Kinds of U.S. Patent Documents. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup> Applicant is to place a check-mark here if English language Translation is attached.

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2001 US

**09/966,958**

**Ping-Hung Lu et al**

09/28/01

1752

U.S. PATENT DOCUMENTS

\*EXAMINER  
INITIAL

DOCUMENT NUMBER

DATE \_\_\_\_\_

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**CLASS**

SUBCLASS

FILING DATE

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## FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER

DATE \_\_\_\_\_

COUNTRY

**CLASS**

SUBCLASS

TRANSLATION

**YES**

NO

**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)

S.J.L.

Jennifer M. Havard et al, "Photoresists with Reduced Environmental Impact: Water-Soluble Resists Based on Photo-Cross-Linking of a Sugar-Containing Polymethacrylate", American Chemical Society, Vol. 32, 1999, pages 86 - 94

554

Qinghuang Lin et al, "A Water-Castable, Water-Developable Chemically Amplified Negative-Tone Resist", American Chemical Society, Vol. 9, 1997, pages 1725 - 1730

**EXAMINER**

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# INFORMATION DISCLOSURE CITATION

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1752

## U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
S.J.L.	5,858,620	01/12/99	Takeo Ishibashi et al	430	313	
	5,648,196	07/15/97	Jean M. J. Frechet et al	430	270.1	
	5,998,092	12/07/99	Iain McCulloch et al	430	270.1	
	5,536,616	07/16/96	Jean M. J. Frechet et al	430	191	
	5,017,462	05/21/91	Paul Stahlhofen et al	430	325	
	5,532,113	07/02/96	Jean M. J. Frechet et al	430	796	

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

S.J.L.		Tashio Sakamizu et al, Water-Soluble Onium Salts: New Class of Acid Generators for Chemical Amplification Positive Resists", American Chemical Society, Vol. 614, 1995, pages 124 - 136
S.J.L.		Jennifer M. Havard et al, Design of Photoresists with Reduced Environmental Impact. 1. Water-Soluble Resists Based on Photo-Cross-Linking of Poly(vinyl alcohol)", American Chemical Society, Vol. 11, 1999, pages 719 - 725

EXAMINER

Sir J. Lee

DATE CONSIDERED

7-23-'03

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